



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of: Baer et al.) Group No.: 1763
Serial No.: 10/675,697) Examiner: Arancibia
Filed: 09/30/2003) Docket No.: HSJ9-2003-0032US1

For: *"METHOD OF FORMING A READ SENSOR USING PHOTORESIST
STRUCTURES WITHOUT UNDERCUTS WHICH ARE REMOVED USING
CHEMICAL-MECHANICAL POLISHING (CMP) LIFT-OFF PROCESSES"*

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

REQUEST FOR RECONSIDERATION

The Applicants respectfully submit this Request for Reconsideration for entry into the present application in response to the Office Action mailed on 05 April 2007.